

Microvoid® CS-41 and CS-41D the latest in known technology

The CS-41 and CS-41D are Air Control's fourth generation in the continuing development of chemical process stations for the semiconductor industry. Designed to operate with an existing clean room overhead air system, they also can include their own vertical laminar flow clean air module if required.

This new system accommodates up to six inch diameter wafers, and can include fully integrated etch and multi wash sub-systems with mechanical agitation and automated transfer of wafer carriers, all under microprocessor control.

Station Features

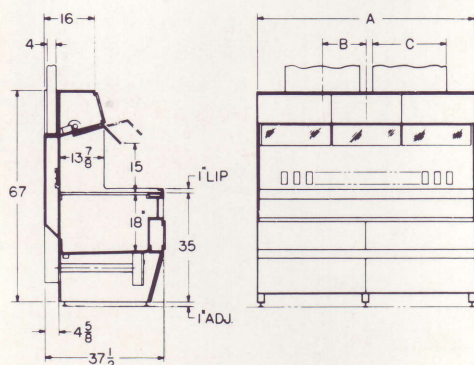
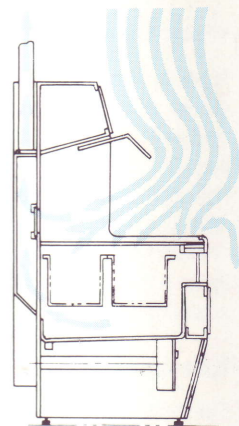
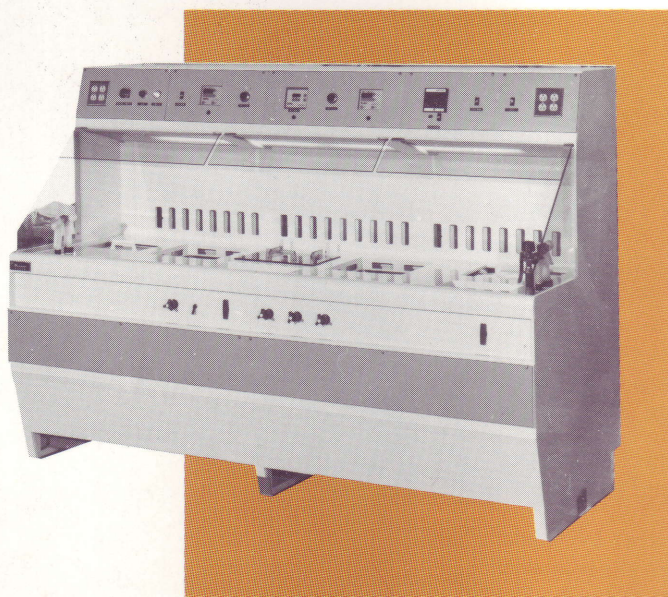
- ☐ All polypro construction for long durability under the most severe chemical environments. Stress relieved material in up to 1 inch thickness, fabricated in an "air-plane wing" cross-braced configuration to insure station rigidity and stability.
- ☐ Modular design, with segmented work surfaces, solid or perforated. Recessed tanks and wells for operator safety, with or without lip exhaust. Work deck and tanks easily removed for servicing.
- ☐ In addition to optional tank lip exhausts and station front lip exhaust, rear located adjustable, segmented louvers provide across-the-work surface exhaust with efficient capture of acid fumes while requiring only a minimum volume of expensive conditioned ambient air.
- ☐ Cabinet depth permits placement of etch tanks handling up to two 6 inch diameter wafer carriers behind multi-wash tanks, for maximum operator safety, minimum station length, and minimum required exhaust volume.
- ☐ Full length exhausted tub beneath work surface, sloped toward one or more 1½ in. drains plumbed to station rear. 18 in. tub depth permits great flexibility in tank design and vertical positioning. Multiple standpipes in tub bottom provide electrical and plumbing communications pathways.
- ☐ Tub and all tanks and sinks have formed, cornerless bottoms and continuous side welds without corner interruptions, to eliminate potential corner leaks and provide exceptionally easy cleaning.
- ☐ Full length rear located exhaust plenum permits coupling to plant exhaust system vertically upward, downward, or horizon-

tally to the rear. Exhaust ports and condensate drain connect plenum to tub.

- ☐ Instrument panel is positioned above work area and angled for comfortable viewing. Panel is segmented, using quick-disconnect fasteners and slide-out restraints for easy servicing.
- ☐ Fluorescent lighting in sealed compartment behind instrument panel illuminates work surface, eliminating shadowed area below instrument compartment.
- ☐ Clear PVC eyeshields formed for optimum operator protection slide in and out to adjust for operator height, and are removable for cleaning (CS-41). Full length hinged transparent eyeshield permits increased access opening height for cleaning and servicing (CS-41D).
- ☐ Inlet supply plumbing in totally enclosed, leak-proof compartment at front of station,

with removable access panel for easy servicing.

- ☐ All electrical wiring to National Electrical Code. Wiring terminates at electrical box with main disconnect switch and individual circuit breakers as required.
- ☐ Base cabinet available in three versions: CS-41D-S, with storage compartment behind sliding doors; CS-41D-C, with roll-out bottle carriers; and CS-41D-P, with an open base covered by a snap-on closure panel, for convenient housekeeping and non-restricted flow of clean air return to station rear or wall registers.
- ☐ All supply and drain plumbing of low corrosion polypropylene, PVC, PVDF or stainless steel according to customer process. Unions installed where necessary for easy disassembly. All lines terminate at station rear.



WIDTH IN.	4 FT.	6 FT.	8 FT.	10 Ft.
A	48	72	96	120
B	—	14	18	22
C	24	24	30	36
WT. (lbs.)	300	450	600	750